

ABSTRACT

C/ The present invention relates generally to cleaning systems, and more specifically to substrate cleaning systems, such as textile cleaning systems, utilizing an organic cleaning solvent and a pressurized fluid solvent. However, unlike conventional cleaning systems, a conventional drying cycle is not necessary. Particularly, the present invention provides a process for cleaning substrates by cleaning the substrates with an organic solvent in absence of liquid carbon dioxide, and removing the organic solvent from the substrates using a pressurized fluid solvent.
